

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of:

Liming Tsau

Appl. No. 09/753,664

Filed: January 4, 2001

For: **High Density Metal Capacitor Using Via Etch Stopping Layer as Field Dielectric in Dual-Damascene Interconnect Process**



Confirmation No.: 1902

Art Unit: 2823

Examiner: Nguyen, Khiem D.

Atty. Docket: 1875.0230000

Request for Reconsideration Under 37 C.F.R. § 1.111

Commissioner for Patents
Washington, D.C. 20231

Sir:

In reply to the Office Action dated **September 24, 2002**, (PTO Prosecution File Wrapper Paper No. 11), Applicant respectfully requests reconsideration of the application identified above. The Reply provided has the following format:

- (A) Starting on a separate page, appropriate remarks and arguments. 37 C.F.R. § 1.121 and MPEP 714

It is not believed that extensions of time or fees for net addition of claims are required beyond those that may otherwise be provided for in documents accompanying this paper. However, if additional extensions of time are necessary to prevent abandonment of this application, then such extensions of time are hereby petitioned under 37 C.F.R. § 1.136(a), and any fees required therefor (including fees for net addition of claims) are hereby authorized to be charged to our Deposit Account No. 19-0036.